

IN THE SPECIFICATION:

Kindly replace the paragraph beginning on page 1, line 3, with the following:

The present invention relates to a plate-making method of a lithographic printing plate. More specifically, it relates to a plate-making method of a lithographic printing plate that enables to prepare a printing plate free from printing stain and excellent in press life and in which safety of a developing solution, stability of developing characteristics with the lapse of time and influence of waste liquid upon the environment are improved.

Kindly replace the paragraph beginning on page 1, line 12, with the following:

A negative-working photosensitive lithographic printing plate widely used hitherto comprises an aluminum plate subjected to hydrophilic treatment having provided thereon a diazo resin layer. In a developing solution for use in the development thereof, an organic solvent is necessarily used and thus, it is anxious for treatment of the waste developing liquid and influence thereof ~~to~~ on the environment. On the other hand, an orthoquinone diazide compound and a novolak resin are used together in a photosensitive layer of a positive-working photosensitive lithographic printing plate, and as a developing solution therefor, an aqueous alkaline solution of silicate capable of dissolving the novolak resin is used. A pH necessary for dissolving the novolak resin is about 13 and the developing solution having such a high pH is required to handle be handled with sufficient caution since it is strongly stimulative when adhered to skin or mucous membrane.

Kindly replace the paragraph beginning on page 2, line 10, with the following:

For instance, a developing solution having a high pH of 12 or more and containing an alkali salt of silicic acid and an amphoteric surface active agent is described in JP-A-8-248643 (the term "JP-A" as used herein means an "unexamined published Japanese patent application") and a developing solution having a high pH of 12 or below and containing an alkali salt of silicic acid with the specified ratio of SiO₂/M₂O (wherein M represents an alkali metal) is described in JP-A-11-65129. The former has a problem in that the image area tends to damage be damaged upon development with the developing solution having such a high pH in addition to the problem of handling as described above. The latter has a problem in that the silicate may be gelled and insolubilized upon a slight decrease in pH of the developing solution during development.

Kindly replace the paragraph beginning on page 3, line 1, with the following:

As a developing solution containing no alkali salt of ~~salieie~~ silicic acid, a developing solution comprising an alkali agent, a complexing agent, an anionic surface active agent, an emulsifying agent and an n-alkanoic acid is described in JP-A-61-109052 and a developing solution comprising an alkali agent, a complexing agent, an anionic surface active agent, an aminoalcohol and an N-alkoxyamine is described in West German Patent 1,984,605. However, these developing solutions damage severely the image area due to the high pH thereof or the organic solvent contained therein and thus, it is difficult to obtain printing characteristics such as press life.

Kindly replace the paragraph beginning on page 3, line 13, with the following:

As a developing solution having a relatively low pH (pH of 12 or below) and containing no alkali salt of salieie silicic acid, an aqueous potassium hydroxide solution containing an anionic surface active agent is described in JP-A-2000-81711 and an aqueous solution of alkali metal carbonate having a pH of 8.5 to 11.5 is described in JP-A-11-65126.

Kindly replace the paragraph beginning on page 6, line 20, with the following:

Further, according to the plate-making method of a lithographic printing plate of the present invention, it is possible to prepare a printing plate free from printing stain and excellent in press life, and the method is preferred in view of safety since a pH of the developing solution is relatively low and enables to improve the influence of waste liquid of the developing solution upon the environment.

Kindly replace the paragraph beginning on page 26, line 22, with the following:

In case of using visible light having a wavelength of 400 nm or more, an Ar laser, a second harmonic wave of a semiconductor laser or an SHG-YAG laser as the light source, various photo-initiators have been proposed. For instance, a certain kind of photo-reducing dyes as described in U.S. Patent 2,850,445, for example, Rose Bengale, Eosine or erythrosine, and a combination system comprising a dye and a photo-initiator, for example, a composite photo-initiator system comprising a dye and an amine as described in JP-B-44-20189, a combination of a hexaarylbimidazole, a radical generator and a dye as

described in JP-B-45-37377, a combination of a hexaarylbiimidazole and a p-dialkylaminobenzylidene ketone p-dialkylaminobenzylidene ketone as described in JP-B-47-2528 and JP-A-54-155292, a combination of a cyclic cis- α -dicarbonyl compound and a dye as described in JP-A-48-84183, a combination of a cyclic triazine and a merocyanine dye as described in JP-A-54-151024, a combination of a 3-ketocoumarin and an activator as described in JP-A-52-112681 and JP-A-58-15503, a combination of a biimidazole, a styrene derivative and a thiol as described in JP-A-59-140203, a combination of an organic peroxide and a dye as described in JP-A-59-1504, JP-A-59-140203, JP-A-59-189340, JP-A-62-174203, JP-B-62-1641 and U.S. Patent 4,766,055, a combination of a dye and an active halogen compound as described in JP-A-63-258903 and JP-A-2-63054, a combination of a dye and a borate compound as described in JP-A-62-143044, JP-A-62-150242, JP-A-64-13140, JP-A-64-13141, JP-A-64-13142, JP-A-64-13143, JP-A-64-13144, JP-A-64-17048, JP-A-1-229003, JP-A-1-298348 and JP-A-1-138204, a combination of a dye having a rhodanine ring and a radical generator as described in JP-A-2-179643 and JP-A-2-244050, a combination of a titanocene and a 3-ketocoumarin dye as described in JP-A-63-221110, a combination of a titanocene, a xanthene dye and an addition-polymerizable ethylenically unsaturated compound having an amino group or a urethane group as described in JP-A-4-221958 and JP-A-4-219756, a combination of a titanocene and a specific merocyanine dye as described in JP-A-6-295061, or a combination of a titanocene and a dye having a benzopyran ring as described in JP-A-8-334897 are illustrated.

Kindly replace the paragraph beginning on page 29, line 4, with the following:

Various kinds of titanocene compounds can be used and, for example, they are appropriately selected from those described in JP-A-59-152396 and JP-A-61-151197.

Specific examples thereof include dicyclopentadienyl-Ti-dichloride, dicyclopentadienyl-Ti-bisphenyl, dicyclopentadienyl-Ti-bis-2,3,4,5,6-pentafluorophen-1-yl, dicyclopentadienyl-Ti-bis-2,3,5,6-tetrafluorophen-1-yl, dicyclopentadienyl-Ti-bis-2,4,6-trifluorophen-1-yl, dicyclopentadienyl-Ti-bis-2,6-difluorophen-1-yl, dicyclopentadienyl-Ti-bis-2,4-difluorophen-1-yl, dimethylcyclopentadienyl-Ti-bis-2,3,4,5,6-pentafluorophen-1-yl, dimethylcyclopentadienyl-Ti-bis-2,6-difluorophen-1-yl and dicyclopentadienyl-Ti-bis-2,6-difluoro-3-(pir-1-yl pyr-1-yl)-phen-1-yl.

Kindly replace the paragraph beginning on page 29, line 17, with the following:

It is known that a photo-initiating function is more improved by adding a hydrogen-donating compound, for example, a thiol compound, e.g., 2-mercaptobenzothiazole, 2-mercaptobenzimidazole or 2-mercaptobenzoxazole, or an amine compound, e.g., N-phenylglycine or an N,N-dialkylamino aromaric aromatic alkyl ester to the photo-initiators described above, if desired.

Kindly replace the paragraph beginning on page 31, line 13, with the following:

By introducing a radical reactive group into the side chain of the organic polymer, the strength of a cured film formed therefrom can be increased. For example, a group having an ethylenically unsaturated bond, an amino group or an epoxy group is illustrated as an addition-polymerizable functional group, a mercapto group, a thiol group, a halogen atom, a triazine structure or an onium salt structure is illustrated as a functional group capable of forming a radical upon irradiation, and a carboxy group or an imido group is illustrated as a polar group. Of the addition-polymerizable functional groups, an ethylenically unsaturated group such as an acryl group, a methacryl group, an allyl group or a stylyl styryl group is particularly preferred. A functional group selected from an amino group, a hydroxy group, a phosphonic acid group, a phosphoric acid group, a carbamoyl group, an isocyanato group, a ureido group, a ureylene group, a sulfonic acid group and an ammonio ammonium group is also useful.